

Presentations of Interest Involving SEZ

8th Symposium on Ultra Clean Processing of Semiconductor Surfaces (UCPSS)

Monday 13.45-14.00, Session 2: CLEANING AND DRYING FOR FEOL APPLICATIONS

■ **Peracetic acid as active species in mixtures for selective etching of SiGe/Si layer systems**

Guder M. , Kolbesen B.O. , Delattre C. , Fischer C. , Schier H.

Tuesday 08.45-09.00, Session 3: FEOL PHOTO RESIST REMOVAL

■ **All-Wet Stripping of FEOL Photoresist Using Mixtures of Sulphuric Acid**

Detterbeck S. , Bellandi E. , Alessandri M. , Henry S. , Archer L. , Hellweg T. , Kagerer

Tuesday 14.00-14.15, Session 6: REMOVAL and DAMAGE

■ **Aging Phenomena in the Removal of Nano-particles from Si Wafers**

Vereecke G. , Veltens J. , Xu K. , Eitoku A. , Arnauts S. , Kenis K. , Snow J. C. Vinckier , Mertens P.W.

Tuesday 15.00-15.15, Session 6: REMOVAL and DAMAGE

■ **Study of a Single-Wafer in Metal Contact Hole Cleaning**

Park J., Song J., Kim H., Cho H., Kim T., Moon B., Rho E., Archer L., Cho W.

Tuesday 15.45-16.00, Session 6: REMOVAL and DAMAGE

■ **The Active Role of Etch Products in Particle Removal by SC-1 Solutions**

Pfeuffer A. , Bensch W. , Lechner A. , Okorn-Schmidt H.